

Strontium Titanate SrTiO_3

Sputtering Targets



Advanced Engineering Materials



Applications

- Ferroelectric
- CMOS
- Thin film capacitor

Features

- High purity
- Custom Sizes Available

Process

- Manufacturing
 - Cold pressed
 - Sintered
 - Elastomer bonded to backing plate
- Cleaning and final packaging
 - Cleaned for use in vacuum
 - Protection from environmental contaminants
 - Protection during shipment

Options

- 99.9% Minimum Purity
- Up to 12.0" Diameter Targets Available
- Planar Tiles Up to 8" X 5" for Larger Target Configurations

Specifications

Typical Analysis - 99.9% (3N) Purity

Metallic Impurities, ppm by weight

Al	Ba	Bi	Ca	Cl	Co	Cr	Fe	Hf	K
<5	<5	<5	<15	<15	<5	<5	<5	<20	<5

Mg	Mn	N	Na	Ni	Pb	S	Sb	Si	Sn
<5	<5	<50	<50	<5	<5	<5	<5	<5	<5

Theoretical Density	5.1 g/cc
Typical Density	3.66 g/cc
Sputter	RF
Max Power Density (Watts/Square Inch)	20
Appearance	White/Beige
Z Ratio	0.31
Particle Size	D50

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